
MATERIALS FLUX FLATTENING IN MAGNETRON SPRAYING SYSTEMS

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Abstract

In order to obtain the films which are uniform in thickness by means of magnetron sputtering technique different approaches are applied. One of the most popular ones is the use of the shaped masking profiles. This work introduces the technique for designing such profiles. The suggested technique is shown in the theoretical form and checked experimentally. For the developed method we have created a module in the python language. In the course of the work we obtained a masking contour providing the deviation from the film thickness uniformity at a level of $\pm 2\%$.

Keywords

Magnetron spraying system, thin films, masking profiles

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